

|   | Type | L # | Hits  | Search Text   | DBs  | Time Stamp          |
|---|------|-----|-------|---|--|---------------------|
| 1 | BRS  | L1  | 680   | (scrub or scrubbing) and<br>plasma and (etch or<br>etching) and semiconductor | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:44 |
| 2 | BRS  | L3  | 335   | photoresist and 1   | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:45 |
| 3 | BRS  | L4  | 35664 | (plasma adj etch) or<br>(plasma adj etching)                                  | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:45 |
| 4 | BRS  | L5  | 304   | 4 and 1   | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:45 |
| 5 | BRS  | L6  | 178   | photoresist and 5   | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:46 |

|    | Type | L # | Hits  | Search Text             | DBs  | Time Stamp          |
|----|------|-----|-------|-------------------------|--|---------------------|
| 6  | BRS  | L7  | 17734 | photoresist same plasma | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:46 |
| 7  | BRS  | L8  | 304   | 1 and 5                 | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:46 |
| 8  | BRS  | L9  | 2694  | low-k                   | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:46 |
| 9  | BRS  | L10 | 8     | 9 and 8                 | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:47 |
| 10 | BRS  | L12 | 7     | wet and 10              | USPAT;<br>US-PGP<br>UB;<br>EPO;<br>JPO;<br>DERWEN<br>T;<br>IBM_TD<br>B | 2004/02/10<br>15:47 |